

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Daniel, Elmer
 Serial Number: 09/887,131
 Filed: 2001.06.22
 Title: Process Independent Alignment Marks
 Examiner: Chris C. Chu
 Group Art Unit: 2815
 Attorney Docket: 01-107

FAX RECEIVED

JAN 27 2003

TECHNOLOGY CENTER 2800

AMENDMENT D

Box AF
 Assistant Commissioner for Patents
 Washington DC 20231

Via fax at 1.703.872.9319

Sir:

In response to the office action dated 2002.11.27, please amend the above-referenced application as follows:

IN THE SPECIFICATION

Please replace the abstract with the following text:

An integrated circuit substrate having a first surface for receiving a series of aligned layers during the creation of the integrated circuit, and a second surface disposed substantially opposite the first surface, where the second surface has at least one alignment mark for aligning the series of aligned layers one to another during creation of the integrated circuit. An apparatus for aligning a mask having an image and at least one complimentary alignment mark to a substrate having a first surface and a substantially opposing second surface, where the substrate has at least one alignment mark on the second surface.